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<b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)		APPLICANT Philip A. Fisher et al.					
FILING DATE 12/14/2001		GROUP ART UNIT 2823					
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
<i>full</i>	A1	6,420,097	07/16/2002	Pike et al.	430	313	05/05/2000
<i>full</i>	A2	6,395,447	05/28/2002	Ishii et al.	430	191	07/27/2000
<i>full</i>	A3	6,358,670	03/19/2002	Wong et al.	430	296	12/28/1999
<i>full</i>	A4	6,319,655	11/20/2001	Wong et al.	430	311	01/11/1999
<i>full</i>	A5	6,200,903	03/13/2001	Oh et al.	438	705	08/20/1999
<i>full</i>	A6	6,174,818	01/16/2001	Tao et al.	438	733	11/19/1999
<i>full</i>	A7	6,057,066	05/02/2000	Hanawa	430	5	07/16/1998
<i>full</i>	A8	5,994,225	11/30/1999	Liu et al.	438	694	10/18/1996
<i>full</i>	A9	5,962,195	10/05/1999	Yen et al.	430	316	09/10/1997
<i>full</i>	A10	5,658,469	08/19/1997	Jennison	438	611	12/11/1995
<i>full</i>	A11	4,446,222	05/01/1984	Kress	430	307	06/21/1982
<i>full</i>	A12	4,394,211	07/19/1983	Uchiyama et al.	438	623	07/08/1982
<b>FOREIGN PATENT DOCUMENTS</b>							
REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION	
						YES	NO
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
	A13	Patent Abstracts of Japan for Japanese Patent Application No. 09252189, 9 April 1999 (1 pg.).					
<i>full</i>	A14	Chiong et al., "Resist contrast enhancement in high resolution electron beam lithography," Journal of Vacuum Science & Technology, Volume 7, No. 6, November 1989, pgs. 1771-1777 (8 pgs.).					
<i>full</i>	A15	Lee et al., "Fabrication of 0.06 $\mu$ m Poly-Si Gate Using DUV Lithography with a Designed Si <sub>x</sub> O <sub>y</sub> N <sub>z</sub> Film as an Arc and Hardmask," Symposium on VLSI Technology Digest of Technical Papers, 1997, pps. 131-132 (2 pgs.).					
<i>full</i>	A16	D. W. Hess and D. B. Graves, "Plasma-Enhanced Etching and Deposition," Microelectronics Processing, (Eds.: D. W. Hess & K. F. Jensen) ACS (1989), Ch. 8 pp. 337-440 (34 pgs.).					
<i>full</i>	A17	Yang et al., "Electronic Beam Processing for Spin-on Polymers and its Applications to Back-End-of-Line (BEOL) Integration," Materials Research Society Symposium Proceedings, Vol. 511, April 1998 (7 pgs.).					
<i>full</i>	A18	PCT International Search Report for PCT/US02/05640 dated 10/02/2002 (7 pgs.).					
<i>full</i>	A19	International Preliminary Examination Report for PCT/US02/05640 dated 07/03/2003 (8 pgs.).					
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<i>Kevin C. Maldonado</i>				12/05/2003			
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include any copy of this form with next communication to applicant.							